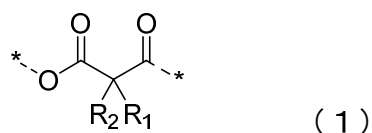


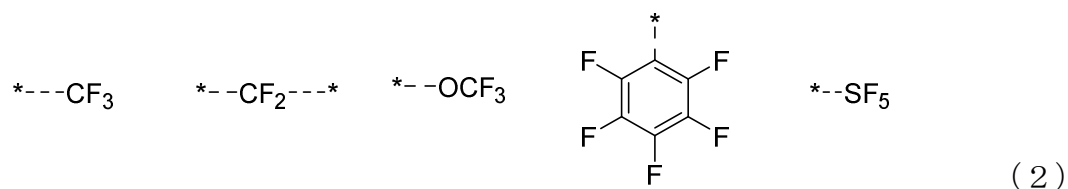
ABSTRACT

TITLE OF INVENTION: COMPOSITION FOR FORMING ORGANIC FILM, METHOD FOR FORMING ORGANIC FILM, PATTERN FORMING METHOD, AND POLYMER

A composition for forming an organic film, containing: (A) a resin or compound; (B) a polymer having a repeating unit of a partial structure (a1) represented by the formula (1); and (C) a solvent. The composition having excellent film-forming properties (in-plane uniformity) , embedding properties on a substrate (wafer), suppressing humps during an EBR step, having excellent process tolerance when used as an organic underlayer film for a multi-layer resist and to provide a method for forming an organic film and a pattern forming method using the composition.



wherein R1 and R2 are hydrogen atoms or saturated or unsaturated organic groups having 1 to 20 carbon atoms, and have at least one fluorine-containing structure represented by the formula (2), at least one of R1 and R2 is an organic group that is not a hydrogen atom, and * represents an attachment point.



[FIG. 1]